AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

LISTING OF CLAIMS:

1. (Currently Amended) A substrate processing device, comprising:

a plurality of vacuum process chambers, each of which administers a prescribed process to a substrate therein;

a through-chamber which constitutes a vacuum chamber, the plurality of vacuum process chambers are hermetically-connected to a perimeter of the through-chamber;

a carry system which carries a substrate in sequence, via the through-chamber, to the plurality of vacuum process chambers, the carry system comprises a substrate holder which holds the substrate upright in such a way that a plate surface thereof forms an angle to the horizontal of between 45° and 90°; and

a horizontal movement mechanism which moves the substrate holder via the through-chamber to the plurality of vacuum process chambers; and

an alignment chamber hermetically connected to the through chamber;

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wherein when the substrate holder is in the alignment chamber, the horizontal movement mechanism is able to move the substrate holder such that a substrate being held in the substrate holder is able to move sideways with respect to a longitudinal direction of the plate surface thereof, as well as in the longitudinal direction thereof so as to align the carry system with the through-chamber.

- 2. (Original) The substrate processing device described in Claim 1, wherein the through-chamber constitutes a direction-altering chamber comprising a direction-altering mechanism which alters the direction of movement of the substrate holder using the horizontal movement mechanism, wherein the direction-altering mechanism alters the direction of movement by rotating the substrate holder and the horizontal movement mechanism about a vertical rotating axis.
- 3. (Original) The substrate processing device described in Claim 2, wherein the direction-altering mechanism rotates the substrate holder and the horizontal movement mechanism about a rotating axis coincident with a center axis of the direction-altering chamber.

- 4. (Original) The substrate processing device described in Claim 1, wherein the substrate holder holds two substrates simultaneously.
- 5. (Original) The substrate processing device described in Claim 4, wherein the substrate holder holds the substrates upright in such a way that the plate surface thereof forms an angle to the horizontal of between 60° and 90° .
 - 6. (Currently Amended) A substrate processing device, comprising:

a plurality of through-chambers, each of which includes a hermetically-connected vacuum chamber;

a plurality of processing chambers that are hermetically-connected to the plurality of through-chambers;

a carry system that carries a substrate in sequence to the processing chambers, the carry system comprises a substrate holder which holds the substrate upright in such a way that a plate surface thereof forms an angle to the horizontal of between 45° and 90°; and

a horizontal movement mechanism which moves the substrate holder to each of the processing chambers via at least a plurality of the through-chambers; and

an alignment chamber hermetically connected to one of the through chambers;

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wherein when the substrate holder is in the alignment chamber, the horizontal movement mechanism is able to move the substrate holder such that a substrate being held in the substrate holder is able to move sideways with respect to a longitudinal direction of the plate surface thereof, as well as in the longitudinal direction thereof so as to align the carry system with the one through-chamber.

- 7. (Original) The substrate processing device described in Claim 6, wherein the through-chambers each constitutes a direction-altering chamber comprising a direction-altering mechanism which alters the direction of movement of the substrate holder using the horizontal movement mechanism, wherein the direction-altering mechanism alters the direction of movement by rotating the substrate holder and the horizontal movement mechanism about a vertical rotating axis.
- 8. (Original) The substrate processing device described in Claim 7, wherein the direction-altering mechanism rotates the substrate holder and the horizontal movement mechanism about a rotating axis coincident with a center axis of the direction-altering chamber.

- 9, (Original) The substrate processing device described in Claim 6, wherein the substrate holder holds two substrates simultaneously.
- 10. (Original) The substrate processing device described in Claim 9, wherein the substrate holder holds the substrates upright in such a way that the plate surface thereof forms an angle to the horizontal of between 60° and 90°.
- 11. (Currently Amended) A through-chamber having a perimeter to which a plurality of vacuum processing chambers are hermetically-connected, the through chamber comprising:

a vacuum chamber;

a horizontal movement mechanism including a substrate holder for holding a substrate, the horizontal movement mechanism horizontally moves the substrate holder through the vacuum chamber, and the substrate holder holds the abovementioned substrate upright in such a way that the plate surface thereof forms a holding angle to the horizontal of between 45° and 90°, and

a direction-altering mechanism which alters the direction of movement of the substrate holder by rotating the substrate holder and horizontal movement mechanism about a vertical rotating axis; and

an alignment chamber hermetically connected to the through chamber:

wherein when the substrate holder is in the alignment chamber, the horizontal movement mechanism is able to move the substrate holder such that a substrate being held in the substrate holder is able to move sideways with respect to a longitudinal direction of the plate surface thereof, as well as in the longitudinal direction thereof so as to align the carry system with the through-chamber.

- 12. (Original) The through-chamber as described in Claim 11, wherein the direction-altering mechanism rotates the substrate holder and the horizontal movement mechanism about a rotating axis coincident with a center axis of the through-chamber.
- 13. (New) The substrate processing device described in Claim 1, further comprising a heater in the alignment chamber.
- 14. (New) The substrate processing device described in Claim 6, further comprising a heater in the alignment chamber.
- 15. (New) The substrate processing device described in Claim 11, further comprising a heater in the alignment chamber.